

Title (en)

APPARATUS AND METHOD FOR MONITORING DEPOSITION IN SYSTEMS CONTAINING PROCESS LIQUIDS

Title (de)

VORRICHTUNG UND VERFAHREN ZUR ÜBERWACHUNG VON ABLAGERUNGEN IN SYSTEMEN MIT PROZESSFLÜSSIGKEITEN

Title (fr)

APPAREIL ET PROCÉDÉ DE CONTRÔLE DE DÉPÔT DANS DES SYSTÈMES CONTENANT DES LIQUIDES DE TRAITEMENT

Publication

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Application

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Abstract (en)

[origin: WO2009034236A1] The present invention relates to an apparatus for monitoring deposition in systems containing process liquids, e.g. process waters. The invention also relates to the use of said apparatus and a method for monitoring deposition on surfaces. The invention also relates to feeding of deposition inhibitors. Said apparatus comprises an overflow holder (2) for gathering liquid (L) from the liquid process, a discharge unit (3) for leading liquid (L) from said overflow holder (2), a flow meter unit (4) connected to said discharge unit (3) for measuring rate of flow for monitoring deposition on surfaces.

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Citation (search report)

See references of WO 2009034236A1

Citation (examination)

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